

## PATENT ABSTRACTS OF JAPAN

(11)Publication number:

61-205933

(43) Date of publication of application: 12.09.1986

(51)Int.Cl.

G03C 1/72 CO8K 5/28

CO8L 61/10

G03F 7/08

(21)Application number: 60-046116

(71)Applicant: KONISHIROKU PHOTO IND CO LTD

(22)Date of filing:

08.03.1985

(72)Inventor: YAMAMOTO TAKESHI

SASA NOBUMASA

**AOKI TORU** 

## (54) PHOTOSENSITIVE COMPOSITION

## (57)Abstract:

PURPOSE: To obtain the title composition having an excellent safe life and ball pen resistance properties and a less decrease in the sensitivity and having a broad developing allowability. By incorporating a novolak resin having a specific weight average molecular weight and a specific degree of a dispersion together with an o-quinone diazide compd. to the title composition.

CONSTITUTION: The title composition comprises the o-quinone diazide compd. and the novolak resin having 6.0× 103W2.0×104 weight average molecular weight and 2W14 ratio of Mw/Mn (the ratio of the Mw and the number average molecu lar weight Mn) (the ratio of dispersion). The sensitive lithographic plate and the photoresist having the photosensitive layer using the composition as mentioned above, is exposed with a light source such as a super high pressure mercury lamp through a transparent positive image film, and is developed with an alkaline developer, thereby remaining only an unexposed part on the surface of the substrate and obtaining a positivepositive type relief image. The title composition having the good oily ball pencil resistance and the safe- life, and the excellent under-developing and over-developing properties and the broad developing allowability is obtd. without depressing the sensitivity of the title composition.

## LEGAL STATUS

[Date of request for examination]

[Date of sending the examiner's decision of rejection]

[Kind of final disposal of application other than the examiner's decision of rejection or application converted registration]

[Date of final disposal for application]

[Patent number]

[Date of registration]

[Number of appeal against examiner's decision of rejection]

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